## **Amendments To The Claims:**

This listing of claims will replace all prior versions, and listings of claims in the application.

## **Listing of Claims:**

- 1. (currently amended) A positive-working radiation-sensitive composition comprising which is characterized in that it is a positive-working radiation-sensitive composition containing a) a compound with an alkali-soluble group protected by an acid labile group a and b) an acid generator which generates acid by irradiation with radiation, and any of the following conditions a1) to a3) are satisified satisfied:[[.]]
- a1) The alkali-soluble group is a carboxyl group and the acid labile group is represented by general formula (1)

$$R^1$$
 $C - R^2$  (1)
 $R^3$ 

 $(R^1 \text{ and } R^2 \text{ are aromatic rings, and } R^3 \text{ represents an alkyl group, a substituted alkyl group, a cycloalkyl group or an aromatic ring; and <math>R^1 \text{ to } R^3 \text{ may be the same or different}[[.]])$ 

a2) The acid labile group is represented by general formula (2)

$$\begin{array}{ccc}
R^4 \\
-C - R^5 & (2) \\
R^6
\end{array}$$

 $(R^4 \text{ to } R^6 \text{ are each an alkyl group, a substituted alkyl group, a cycloalkyl group or an aromatic ring, and at least one of <math>R^4 \text{ to } R^6 \text{ is an aromatic ring with an electron-donating group; and } R^4 \text{ to}$ 

R<sup>6</sup> may be the same or different[[.]])

- a3) The acid labile group a has an alkali-soluble group or alternatively the acid labile group a has an alkali-soluble group protected by an acid labile group b.
- 2. (original) A positive-working radiation-sensitive composition according to Claim 1 where condition a1) is satisfied.
- 3. (currently amended) A positive-working radiation-sensitive composition according to Claim 2 wherein which is characterized in that R<sup>1</sup> to R<sup>3</sup> are each independently an aryl group or a substituted aryl group.
- 4. (original) A positive-working radiation-sensitive composition according to Claim 1 where condition a2) is satisfied.
- 5. (currently amended) A positive-working radiation-sensitive composition according to Claim 4 which is characterized in that wherein the alkali-soluble group in the compound meeting condition a2) is a carboxyl group or a phenolic hydroxy group.
- 6. (currently amended) A positive-working radiation-sensitive composition according to Claim 4 which is characterized in that wherein the aromatic ring with an electron-donating group is of structure represented by general formula (3):[[.]]

$$R^8$$
  $R^9$   $R^{10}$  (3)

 $(R^8,\,R^{10}$  and  $R^{12}$  each independently represents a hydrogen atom, an alkyl group with 1 to 4

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carbons or an alkoxy group with 1 to 6 carbons, and at least one of these represents such an alkyl group or alkoxy group. [[.]]  $R^9$  and  $R^{11}$  each independently represents a hydrogen atom, an alkyl group with 1 to 4 carbons or an alkoxy group with 1 to 6 carbons [[.]]).

- 7. (original) A positive-working radiation-sensitive composition according to Claim 4 where the electron-donating group is an alkoxy group with 1 to 6 carbons.
- 8. (original) A positive-working radiation-sensitive composition according to Claim 1 where condition a3) is satisfied.
- 9. (currently amended) A positive-working radiation-sensitive composition according to Claim 8 which is characterized in that wherein the acid labile group a in the compound meeting condition a3) has at least one phenolic hydroxyl group, or alternatively a phenolic hydroxyl group further protected with acid labile group b.
- 10. (currently amended) A positive-working radiation-sensitive composition according to Claim 8 wherein which is characterized in that the acid labile group a in the compound meeting condition a3) has at least one carboxyl group or alternatively a carboxyl group further protected with acid labile group b.

11. (currently amended) A positive-working radiation-sensitive composition according to Claim 8 wherein which is characterized in that the labile group a in the compound meeting condition a3) group represented by general formula (4):[[.]]

$$\begin{array}{ccc}
 & R^{13} & & \\
 & -C - R^{14} & & \\
 & & R^{15}
\end{array}$$
(4)

( $R^{13}$  to  $R^{15}$  are each independently an alkyl group, a substituted alkyl group, a cycloalkyl group, an aryl group, a substituted aryl group, a group containing an alkali-soluble group protected by acid labile group b, and at least one is a group containing an alkali-soluble group, or a group containing an alkali-soluble group, or a group containing an alkali-soluble group protected by acid labile group  $b_{3}[[.]] R^{13}$  to  $R^{15}$  may be the same or different[[.]]).

12. (currently amended) A positive-working radiation-sensitive composition according to Claim 11 wherein which is characterized in that at least one of R<sup>13</sup> to R<sup>15</sup> in general formula (4) is a group represented by general formula (5) or (6):[[.]]

(A represents an alkylene group with 1 to 4 carbons, an arylene group with 6 to 10 carbons or a single bond, [[.]] B represents an alkylene group with 1 to 6 carbons, an arylene group with 6 to 10 carbons, an alkylenearylene group with 7 to 12 carbons or a single bond, [[.]]  $R^{16}$  to  $R^{19}$  each independently represents a hydrogen atom or an alkyl group with 1 to 4 carbons, [[.]] Y represents an acid labile group b or a hydrogen atom, and m is 1 to 3[[.]]).

13. (currently amended) A positive-working radiation-sensitive composition

according to Claim 11 wherein which is characterized in that at least one of R<sup>13</sup> to R<sup>15</sup> in general formula (4) is a group represented by general formula (7):[[.]]

( $R^{20}$  and  $R^{21}$  each independently represents a hydrogen atom or an alkyl group with 1 to 4 carbons, [[.]] Y represents an acid labile group b or a hydrogen atom, and m is 1 to 3[[.]]).

14. (currently amended) A positive-working radiation-sensitive composition according to Claim 11 wherein which is characterized in that at least one of R<sup>13</sup> to R<sup>15</sup> of general formula (4) is of structure represented by general formula (8):[[.]]

( $R^{22}$  and  $R^{23}$  represent a hydrogen atom or an alkyl group with 1 to 4 carbons,[[.]] Y represents an acid labile group b or a hydrogen atom[[.]]).

15. (currently amended) A positive-working radiation-sensitive composition according to Claim 1 wherein which is characterized in that the compound meeting any of conditions a1) to a3) is a polymer of weight average molecular weight from 5,000 to 50,000.

16. (currently amended) A positive-working radiation-sensitive composition according to Claim 1 wherein which is characterized in that the compound meeting any of conditions a1) to a3) is a polymer containing structural units represented by general formula (9):[[.]]

$$-CH2-C-C (9)$$
COOZ

( $\mathbb{R}^{24}$  represents a hydrogen atom, an alkyl group with 1 to 4 carbons, a cyano group or a halogen,[[. ]] Z is a group represented by general formula (1), (2) or (4)).

17. (currently amended) A positive-working radiation-sensitive composition according to Claim 4 or Claim 8 wherein which is characterized in that the compound meeting condition a2) or a3) is a polymer containing structural units represented by general formula (10):[[.]]

$$-CH_2-C$$

$$OX$$

$$(10)$$

(R<sup>23</sup> represents a hydrogen atom, an alkyl group with 1 to 4 carbons, a cyano group or a halogen,[[.]] X is an acid labile group represented by general formula (2) or (4)).

- 18. (currently amended) A positive-working radiation-sensitive composition according to Claim 16 wherein which is characterized in that R<sup>24</sup> is a cyano group or a halogen.
- 19. (original) A method for the production of a pattern in which a positive-working radiation-sensitive composition according to Claim 1 is applied onto a substrate which is to

undergo processing, and drying, exposure and development carried out.

20. (currently amended) A method of pattern production according to Claim 19 wherein which is characterized in that the exposure is carried out by means of an electron beam.